

Attorney Docket # 10961260-3

**CLAIM REJECTIONS - 35 U.S.C. §102(b)**

Claims 1,2 and 4-6 have been rejected under 35 U.S.C. 102(b) as being anticipated by Kawakita.

Deep region oxides that were separated from each other were a problem in prior art (column 4, lines 4-5). This was a problem solved by the Kawakita isolation structure (column 4, lines 15-16). Kawakita teaches connecting the deep region oxides into a single continuous layer (column 3, lines 61-63), and specifically teaches away from non-continuous deep regions of oxide.

In Kawakita, the substrate 22 is etched out to form the deep regions 40 of the isolation structure (Figure 2g). Next, the continuous oxide layer 42 is formed (Figure 2h). Finally, devices 52, 54 are formed on top of the oxide layer (Figure 2j). Since the devices are formed on top of a continuous oxide layer, there is no contact whatsoever between the device and the substrate. The devices are completely isolated from the substrate by the underlying oxide of the isolation structures (Figure 2j; Column 5, lines 26-27 and lines 41-43).

In distinct contrast to the prior art, the deep region oxide of the present invention is not in contact with other deep regions, so it does not form a continuous deep region layer underneath the devices (Figure 3). Therefore, the devices 302, 304 remain in contact with the substrate (Figure 3; page 8, lines 8-9). This novel feature specifically goes against the teachings of Kawakita, and can be found in claims 1 and 5, which now recite that each device is "in contact with the substrate". Claims 1 and 5 are believed to be allowable based on the novel feature cited within. Applicants respectfully submit that claims 1 and 5 are patentably distinct over the prior art.

Dependent claims 2 and 4 are believed to be allowable based on the allowability of claim 1. Dependent claim 6 is believed to be allowable based on the allowability of claim 5.

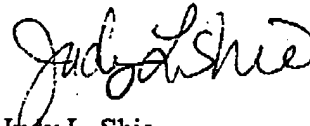
In summary, the claims are distinct and patentable over Kawakita, due to the above-mentioned novel features. The rejections under 35 U.S.C. §102(b) are believed to be overcome. Applicants respectfully request that the rejection be reconsidered and withdrawn.

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**CONCLUSION**

If the Examiner has any further questions or would like to discuss this application in more detail, he is invited to call the Applicants' agent at the telephone number given below. The Applicants respectfully suggest that the claims presently in the application are distinct over the prior art and that the application is now in condition for allowance. Accordingly, the Applicants solicit favorable action.

Respectfully submitted,  
Min Cao, et al.



Judy L. Shie  
Patent Reg. No. 50,305

February 11, 2003  
Agilent Technologies  
Intellectual Properties Administration  
Legal Department, M/S DL-429  
815 SW 14<sup>th</sup> Street  
Loveland, CO 80537  
(408) 345-8920

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